1st Announcement and Call for Papers

Photomask Japan 2021

The 27th Symposium on Photomask and NGL Mask Technology

From Monday, April 26 through Wednesday, April 28, 2021

PACIFICO Yokohama, Yokohama, Kanagawa, Japan

Symposium Chair:

Prof. Takeo Watanabe
University of Hyogo

Abstract Due Date:
November 30, 2020

Manuscript Due Date:
March 31, 2021

Photomask Japan 2021 is the 27th international symposium on photomasks and NGL masks in Japan. The aim of the symposium is to bring together engineers and researchers from Japan, USA, and all over the world in the field of photomasks, NGL masks and related technologies to discuss recent progress, applications, and future trends. The symposium program will feature invited papers, contributed papers, poster sessions, and the popular panel discussion. Exhibit opportunities will be provided to mask design, manufacturing, materials, and equipment companies.

Papers are solicited on the following and related topics:

- **Materials for photomasks**
- **Fabrication process steps and equipment for photomasks (developing, etching, cleaning etc.)**
- **Photomask writing tools and technologies including multi-beam EB writer**
- **Tools and technologies for metrology/ inspection/ repair**
- **Technologies and Infrastructures for EUVL/ NIL/ FPD masks**
- **EDA, MDP, curvilinear ILT and DTCO**
- **Photomasks with RET: PSM, OPC, SMO and multiple patterning**
- **Photomask-related lithography technologies**
- **NGL mask technologies and their applications: DSA and others**
- **Strategy and business challenges: cost, cycle time and total mask solutions**
- **Patterning technologies for semiconductor and electronic devices**
- **Semiconductor manufacturing technologies**
- **eBeam direct writing and eBeam lithography technologies**
- **Photomask and lithography related technologies in academia (poster session)**

Detailed information will be announced in the 2nd Call for Papers. Manuscripts are required of all accepted applicants and must be submitted in English.

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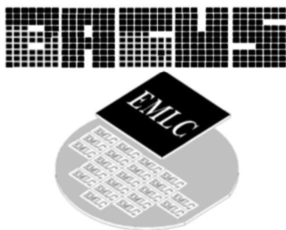

Abstract Submission

All authors are *strongly encouraged* to submit their abstract by the due date, November 30 2020 via the PMJ official website.

Abstract submission Web page will be opened in October 2020 at:

http://www.photomask-japan.org/

Further information and instructions will be made available at the 2nd Announcement & Call for Papers, which will be published around September, 2020

***Please do not send the abstract by e-mail or facsimile.**

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